

Photomask Japan 2019

Best Paper Award Winners



Best Oral Presentation:

| Program No. | Presentation Title | Name | Affiliation |
|------------------|--|---|----------------------------------|
| 5-4 | ASML NXE Pellicle Update | Derk Brouns, Par Broman, Jan-Willem van der Horst, Raymond Lafarre, Raymond Mass, Theo Modderman, Guido Salmaso | ASML BV (The Netherlands) |
| 2-3 [BACUS] | Development of Plasma Etching Process Using Machine Learning | Takeshi Ohmori, Hyakka Nakada, Masayoshi Ishikawa, Naoyuki Kofuji, Tatehito Usui, Masaru Kurihara | Hitachi, Ltd. R&D Group (Japan) |
| 4-3 | Multi-beam mask writer MBM-1000 | Hiroshi Matsumoto, Hayato Kimura, Takao Tamura and Kenji Ohtoshi | NuFlare Technology, Inc. (Japan) |

Best Poster Presentation:

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| 10A-1 [EMLC] | aquaSAVE™: Antistatic Agent for Electron Beam Lithography | Takahiro Mori, Akira Yamazaki | Mitsubishi Chemical Corporation (Japan) |
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Best Academic Poster Presentation:

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| 10S-6 [BACUS] | Development of an EUV and OoB Reflectometer in NewSUBARU Synchrotron light Facility | Keisuke Tsuda, Tetsuo Harada, Takeo Watanabe | University of Hyogo, LASTI, Center for EUV Lithography (Japan) |
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